

IN THE SPECIFICATION

Please replace the paragraph at page 15, lns. 14-15 with the following amended paragraph:

Then, second conductive layers (source and drain wirings) 23 to 28 are formed under reduced pressure by in-jet. FIG. ~~[[1D]]~~ 2D shows a cross-sectional view at this point.

Please replace the abstract at page 46 with the following amended abstract:

To provide a method for manufacturing a wiring, a conductive layer, a display device, and a semiconductor device, each of which can meet a large sized substrate and which is manufactured with a higher throughput by using a material efficiently, the conductive layer is formed over the substrate having an insulating surface by discharging the conductive material, and heat treatment is performed by a lamp or a laser beam over the conductive layer. Furthermore, the conductive film is formed under ~~reduces~~ reduced pressure according to the present invention.